Supplies Provided by NUFAB

**Gowning**
All required gowning supplies

**Personal Protective Equipment (PPE)**
All required PPE

**Chemicals**
Photoresists: SPR220.7, SU8-2050, SU8 25, SU8 3025, SU8 2, SU8-2010, S1813, S1805, LOR 1A, LOR 5A, AZ 5214E-IR, AZ P4620, 495 PMMA A8, Polyimide PI2545, AZ nLOF2035
Developers: MF319, AZ 400K (1:4 and concentrated), SU8 Developer, AZ 917MIF, AZ 300MIF
Resist Removers: Remover 1165, Nanostrip
Adhesion Promoter: HMDS, MCC Primer 80/20 (20% HMDS and 80% PM Acetate)
Solvents: Acetone, 2-Propanol
Etchants: Chrome Etchant, Buffered Oxide Etch 6:1 and 10:1, Aluminum Etchant, Nanostrip, HF, Fe₂O₃ Etchant, Copper Etchant, Gold Etchant TFA, KOH, TMAH 25%, HBr, HCl, Citric acid, H₂SO₄, HNO₃, H₃PO₄,

**General Cleanroom Supplies**
Silicon Wafers (various sizes)
Wafer and Mask Holders (various sizes)
Cleanroom Notebooks
Cleanroom Paper
Cleanroom Wipes (two types)
Storage Boxes
Petri Dishes
Aluminum Foil

**Equipment Specific Supplies**
AJA Sputter Targets: Cu, Al, Cr, Ti, Ni, W, Si, SiO₂, Si₃N₄, ZnO, ITO, PZT, Ag
AJA E-beam Evaporator: Crucibles for all materials
Denton Thermal Evaporator: Boats for all materials, chrome-coated tungsten rods
Evaporation Materials: Mo, W, Ag, Al, Cu, Ni, Ti, Cr, Au
Mask and Maskless Aligners: Blank Photomasks (for mask making) 4”x4” (Cr), 5”x5” (Cr), 3”x3” (Fe₂O₃), 4”x4” (Fe₂O₃), 5”x5” (Fe₂O₃)

**Gases**
Silane, Ammonia, Hydrogen, Dichlorosilane, Forming Gas (4%H₂, Balance N₂), UHP nitrogen, Oxygen, N₂O, CF₄, C₄F₈, CHF₃, Helium, SF₆, Argon, Liquid CO₂

Updated: 5/14/2018